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in part

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re U.S. Patent Application of: ) Attorney Docket: 4425-168

)

Yen-Ting Lu ) Group Art Unit: 1756

)

Serial No.: 09/919,868 ) Examiner: C. G. Young

)

Filed: August 2, 2001 )

**RECEIVED**

**MAY 27 2003**

**TC 1700**

For: METHOD FOR REDUCING LINE EDGE  
ROUGHNESS OF PHOTORESIST

AMENDMENT

Honorable Commissioner for Patents  
Washington, D.C. 20231

Sir:

This is in response to the Office Action of February 21, 2003, in connection with the above-identified application.